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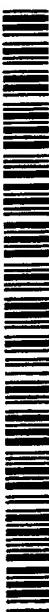
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(54) Title: METHOD OF FORMING A MASKING PATTERN ON A SURFACE

(57) Abstract: A method of forming a masking pattern on a surface using the technique of droplet ejection to deposit droplets of deposition material, said method comprising depositing a plurality of droplets on said surface to form such a pattern comprising multiple discrete or coalesced extended portions.